


<b>INFORMATION DISCLOSURE CITATION</b> PTO-1449 		Atty. Docket No. NMTc-0756	Serial No. 10/016,837	RECEIVED JUL 16 2002 TECHNOLOGY CENTER 2800
		Applicant ZHANG, Youping	Group 2825	
Filing Date 12/12/2001				
<b>OTHER DOCUMENTS (Including Author, Title, Date, Pertinent Pages, Etc.)</b>				
EXAMINER'S INITIALS	CITATION			
BB	Ackmann, P., et al., "Phase Shifting and Optical Proximity Corrections to Improve CD Control on Logic Devices in Manufacturing for Sub 0.35 um I-Line", SPIE, Vol. 3051, pp. 146-153, March 12-14, 1997.			
BB	Lithas, "Lithas: Optical Proximity Correction Software" (2 pages).			
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BB	Rieger, M., et al., "Mask Fabrication Rules for Proximity-Corrected Patterns", Precim Company, Portland, Oregon (10 pages).			
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BB	Cobb, et al., "Fast Sparse Aerial Image Calculation for OPC", SPIE, Vol. 2621, pp. 534-544, September 20-22, 1995.			
BB	Lucas, K., et al., "Model Based OPC for 1st Generation 193nm Lithography", Motorola Inc., IDT assignee to IMEC (12 pages).			
BB	Stirniman, J., et al., "Quantifying Proximity and Related Effects in Advanced Wafer Processes", Precim Company, Hewlett Packard Labs (9 pages).			
BB	Sugawara, M., et al., "Practical Evaluation of Optical Proximity Effect Correction by EDM Methodology", Sony Corporation (11 pages).			
BB	Saleh, B., et al., "Reduction of Errors of Microphotographic Reproductions by Optimal Corrections of Original Masks", Optical Engineering, Vol. 20, No. 5, pp. 781-784, September/October 1981.			
BB	Fu, C.C., et al., "Enhancement of Lithographic Patterns by Using Serif Features", IEEE, Transactions On Electron Devices, Vol. 38, No. 12, pp. 2599-2603, December 1991.			
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BB	Rieger, M., et al., "System for Lithography Proximity Compensation", Precim Company, Portland, Oregon, September 1993 (28 pages).			

EXAMINER: Bundh/BrownDate Considered: 3/3/04

EXAMINER: Initial if reference considered, whether or not citation is in conformance with MPEP § 609; draw line through citation if not in conformance and not considered. Include copy of this form with next communication to applicant.

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<b>EXAMINER'S INITIALS</b>	<b>CITATION</b>				
BB	Stirniman, J., et al., "Fast Proximity Correction with Zone Sampling", SPIE, Vol. 2197, pp. 294-301 (1994).				
BB	Stirniman, J., et al., "Optimizing Proximity Correction for Wafer Fabrication Processes", SPIE, Photomask Technology And Management, Vol. 2322, pp. 239-246 (1994).				
BB	Stirniman, J., et al., "Wafer Proximity Correction and Its Impact on Mask-Making", Bacus News, Vol. 10, Issue 1, pp. 1, 3-7, 10-12, January 1994.				
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BB	Asai, N., et al., "Proposal for the Coma Aberration Dependent Overlay Error Compensation Technology", Jpn. J. Appl. Phys., Vol. 37, pp. 6718-6722 (1998).				

EXAMINER: Bamber BermanDate Considered: 3/3/04

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 PATENT & TRADEMARK OFFICE 8501

FOREIGN PATENT DOCUMENTS							
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bb	JP 3-80525	4/5/1991	JP			<input type="checkbox"/>	<input type="checkbox"/>
br	WO 00/67074 A1	11/9/2000	WO			<input type="checkbox"/>	<input type="checkbox"/>
bb	GB 2,324,169 A	10/14/1998	GB			<input type="checkbox"/>	<input type="checkbox"/>


EXAMINER:

Brian Boney

Date Considered:

3/3/04

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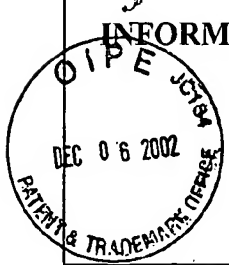
**U.S. PATENT DOCUMENTS**

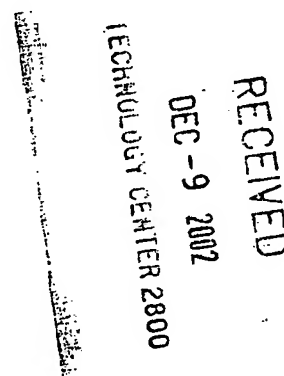
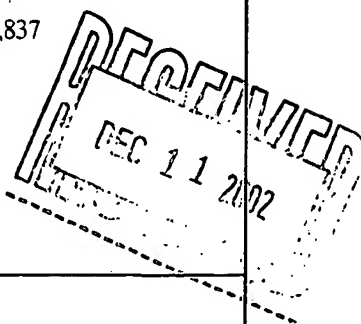
EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
BB	5,631,110	5/20/1997	Shioiri, et al.	430	5	6/5/1995
BB	5,682,323	10/28/1997	Pasch, et al.	364	491	3/6/1995
BB	5,723,233	3/3/1998	Garza, et al.	430	5	2/27/1996
BB	5,815,685	9/29/1998	Kamon	395	500	9/15/1995
BB	5,825,647	10/20/1998	Tsudaka	364	167.03	3/12/1996
BB	5,991,006	11/23/0199	Tsudaka	355	53	10/27/1997
BB	6,081,658	6/27/2000	Rieger, et al.	395	500.22	12/31/1997
BB	6,289,499	9/11/2001	Rieger, et al.	716	21	1/7/2000
BB	6,243,855 B1	6/5/2001	Kobayashi, et al.	716	19	9/29/1998
BB	6,249,597 B1	6/19/2001	Tsudaka	382	144	12/17/1998

EXAMINER: Brenda Brown

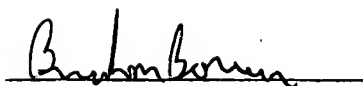
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EXAMINER'S INITIALS	PATENT NO.	DATE	NAME	CLASS	SUBCLASS	FILING DATE
BB	6,014,456	1/11/2000	Tsudaka	382	144	7/15/1996
BB	6,154,563	11/28/2000	Tsudaka	382	144	12/17/1998
BB	6,298,473 B1	10/2/2001	Ono, et al.	716	21	12/3/1998
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BB	2002/0100004 A1	7/25/2002	Pierrat, et al.	716	5	3/15/2002



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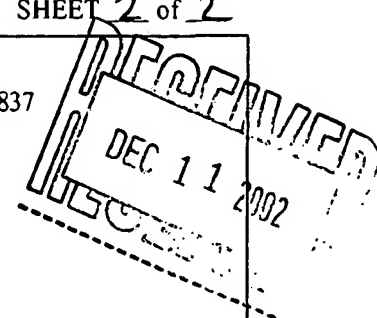
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BB	Cobb, N., et al., "Fast, Low-Complexity Mask Design", SPIE, Vol. 2440, pp. 313-327, February 22-24, 1995.
BB	Cobb, N., et al., "Experimental Results on Optical Proximity Correction With Variable Threshold Resist Model", SPIE, Vol. 3051, pp. 458-468, March 12-14, 1997.
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